

# Photoresist-Stripper SVD - VLSI grade

## Photoresist-Stripper SVD (C-JV-DY)

easily removes layers of photoresists (PR) from inorganic substrates such as silicon, glass and metals (e.g. copper). The smart intelligent fluids® (IF) mode of action is not based on aggressive dissolving processes as in the case of many conventional products. Instead, intelligent fluids® enable a gentle physical detaching even of persistent layers, without damaging the substrate surface.

The **Photoresist-Stripper SVD** with its highly dynamic phase structures works in two steps:

- infiltration and fragmentation of the layer
- wrapping and removal of fragments

Negative-tone photoresists will be detached in larger fragments and can be filtered off. Positive-tone photoresists on the other hand will be incorporated into the fluid.

### Advantages:

- water-based
- pH neutral to the skin (pH: 5.5 – 6.5)
- non-toxic, non-flammable
- safe-to-handle
- dermatologically tested - "excellent"
- readily biodegradable

## Application

Apply IF directly and undiluted onto the surface.

Compatible with single-wafer and batch-spray equipment. For wet-benches bath-agitation is necessary.

Temperature range: 30 °C to 70 °C, **recommended 40 °C to 60 °C**



Time for removal of PR is depending on type and lithography parameters. It may vary from 1 min to 15 min, seldom longer.

Rinse surface properly with water, ethanol or isopropanol. For single-wafer-rinse higher spin-speed is recommended.

## Remarks

Photoresist-Stripper SVD should be used up within 6 months from the date of delivery. We can not guarantee a longer time for VLSI-quality after the product leaves our premises. However, a storage beyond this point does not necessarily mean that the product is unusable (shelf-life from date of manufacturing: one year). This intelligent fluid® was not developed for cleaning processes such as post-CMP clean or particle removal. The recommended application form is by batch- or single-wafer treatment, process parameters (tools, time, temperature) should be optimised individually in previous tests.

## Important Note

Store in original container only. IF should not be diluted. It could influence its properties and destroy its dynamic structures. IFs do not evaporate without residues, rinsing step is necessary. Please follow the instructions in the material safety data sheet for proper use, storage and disposal. The information given here are up to date and are subject to change in the future without prior notice.